

次観測装置用の新しい回折格子の開発状況 VI

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Reflection and transmission grating

- ·Diameter of a ca as the disperser. era lens exceeds maximum size (φ440) of calcium fluoride if a reflection grating is used
- →Transmission grating can reduce size of the camera lens (→total optical system)
- →Transmission grating is able to realize perfect Littrow mounting.



WFOS: Wide Field Optical Spectrograph



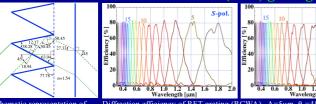




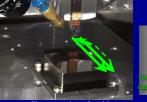
The first generation instrument for TMT. R= 500~5,000 (150~7.500 goal) @0.75" slit

1.6

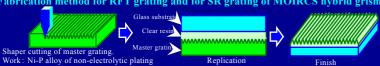
Reflector facet transmission (RFT) grating



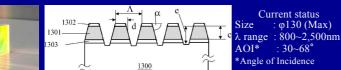
Diffraction efficiency of RFT grating (RCWA).

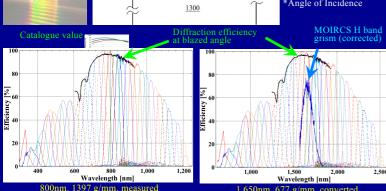


Fabrication method for RFT grating and for SR grating of MOIRCS hybrid grism



LightSmyth Transmission Grating for MOIRCS J and H band grisms instead of VPH grisms

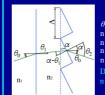




Measurement for diffraction efficiency at blazed angle

Measurement for efficiency of super blaze

Limitation of surface relief (SR) transmission grating



 $n = 1.8, \ \theta_0 \le 36^{\circ}$ $n = 1.8, \ \theta_0 \le 36^{\circ}$ $n = 2.3, \ \theta_0 \le 45^{\circ}$ $n = 3.0, \ \theta_0 \le 54^{\circ}$

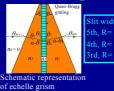
Fabrication process of the volume binary grating

VPH grating

- VPH (Volume Phase Holographic) grating, in which refractive index is modulated sinusoidally achieves diffraction efficiency up to 100% for S or P polarization
- characteristics of diffraction efficiencies are different between
- Diffraction efficiencies of VPH grating decrease in higher
- orders.
 VPH grating is not feasible for an echelle grating.



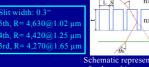
Echelle grism (Volume binary grating) for MOIRC



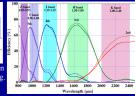
patterning onto SOQ* substrate

glass plate by filling high-index

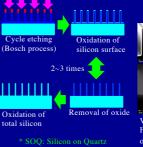
resin (n~1.72)







Diffraction efficiency of binary grating (RCWA). 4.6:0.5 $[\mu m]$, θ_0 =28.4 $^{\circ}$, n_2 =1.6, n_3 =1.6, t=16 μm .

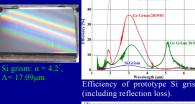


Volume binary grating of silicon. Fabricated by Nanotechnology platform of Toyota Institute of Technology.

Grism for MIMIZUKU







SEM photograph of Ge grism.

(including reflection loss)

Summary			
	Optimal Order	Eff. [%] (λ-λ μm)	Status of development
RFT grating	2 th ~	~ 80 (0.3~2.4)	Performed diamond shaper cutting of master gratings. Planning the third trial fabrication in this April.
Hybrid grism	2 rd ∼	~ 70 (0.3~2.4)	Performed diamond shaper cutting of a master grating and replication. Planning fabrication of optimum master grating for MOIRCS medium dispersion grism in this March.
LightSmyth Grating	1 st	~ 100 (0.8~3.0)	Ordered numerical calculations of performance evaluation for MOIRCS J and H band grisms and samples.
Volume binary (VB) grating	1 st ∼	~ 80 (0.2~3.0)	Performing replication test by using a Si grating and test fabrications of silica VB gratings by using the new technique.
Si or Ge grism	1 st	~ 80 (1.2~14)	Performed direct diamond cutting of Si grisms. Planning fabrication of a Si and Ge grisms in this November.

Acknowledgements

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